

- Low cost, computer controlled deposition system
- S&A 250B Network Analyzer Monitor Crystal Measurement System
- Quartz crystal sensor and substrates rotate on the same spherical radius for accurate thickness deposition control (Patent No. 6,090,444)
- Pneumatic actuated source shutter for precise deposition termination
- Each substrate holder can be plated to a different thickness in the same deposition cycle
- Mechanical assemblies shielded from deposition material are easily removed for cleaning



- Low profile bell jar assembly for easy operator access
- Supports various mask systems
- Substrate heater
- RF plasma bombard
- Plating units: Å, Hz, F², Å of Si O₂
- Fast pump down time for high system throughput

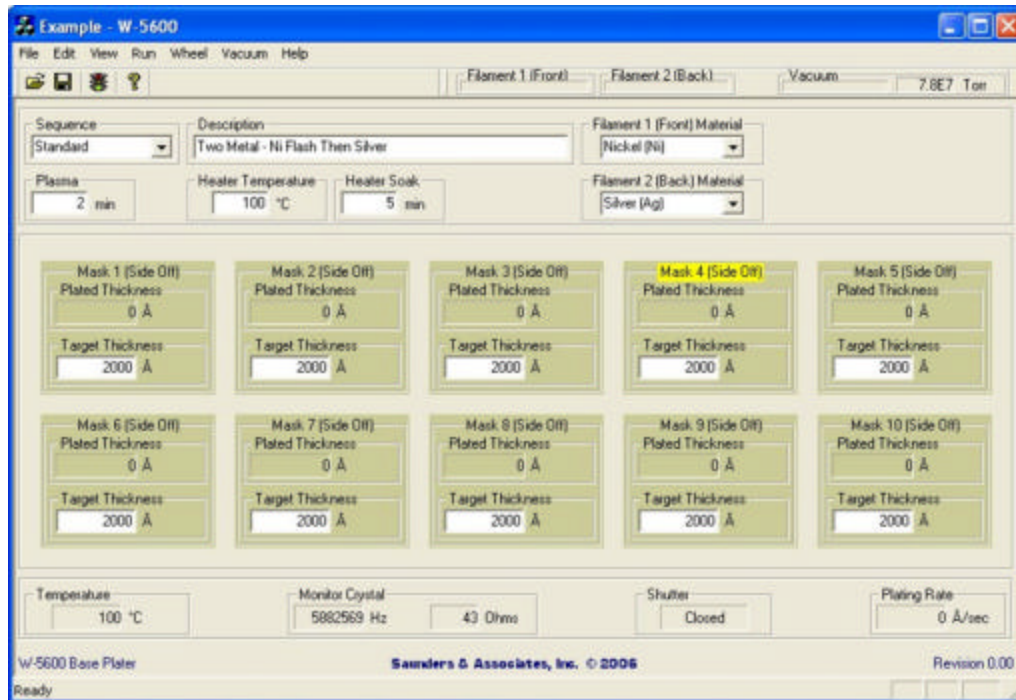
SPECIFICATIONS

Thickness Uniformity:

2% of total deposition, typical

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Main Screen Display showing each mask status and deposition target.

SYSTEM CONFIGURATION

- Direct Drive Roughing Pump
- Cryo or Diffusion Pump
- Automatic Mask Flipping Mechanism
- Two Metal, 3 Layer Capability
- Substrate Heater
- S&A 250B Network Analyzer
- Plasma Cleaning
- Light pole
- Computer
- *Windows*[®] based System Software
- Printer (optional)

FACILITY REQUIREMENTS

- **Power:** 380V or 208V 3-PHASE, 7 KVA, 50/60 Hz
- **Inlet Pressures:**
 - **Air:** 90 – 100 PSIG
 - **Nitrogen:** 70 – 100 PSIG
 - **Argon/Oxygen 80/20 (plasma cleaning):** 10 PSIG
- **Cryo Pump Water Cooling:** 0.50 GPM @ 60° – 80°F
- **Diffusion Pump Water Cooling:** 0.25 GPM @ 60° – 80°F
- **Dimensions:** W 53 x D 34 x H 67.5 Inches
(excluding Cryo Compressor)

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